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## PATENTS ABSTRACTS OF JAPAN

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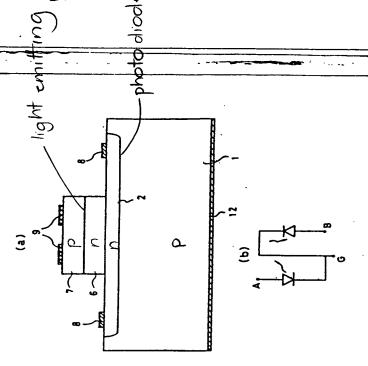
. [51] Int. Cl. H01L27/15,G11B7/135,H01L27/04,H01L27/14,H01L31/12,H01L33/00,

To enable a light-emitting element and a light-receiving element to be compound in a simple structure by setting a light-emitting diode or a main terminal of one of a laser diode and a photo diode to a common potential H01S3/18, H04N1/024, H04N1/028 without using a wiring. PURPOSE:

as a photo diode and is used as a light-receiving element. A light-emitting diode is formed as a second conductive type impurities layer 2. A double-layer gallium arsenide layer is formed on this n-type impurities layer 2, an impurities layer 6 at a side which contacts an Si substrate is formed as an n-type impurities ayer by doping silicon or tellurium, and then beryllium or zinc is doped to between the p-type Si substrate 1 and the n-type impurities layer 2 is formed of GaAs and is used as a light-emitting element and an electrode which is CONSTITUTION: A p-type conductive type silicon is used as a first semiconductor substrate 1 and an n-type impurities layer where phosphor or arsenic is doped an impurities layer 7 on it, thus forming a p-type impurities layer. A pn junction ormed on a from a first main surface of the Si substrate 1 to the n-type impuris formed by the n-type impurities layer 6 and the p-type impurities layer ies layer 2 is used as a common electrode 8.

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